Supplemental Document "High growth-rate atomic layer deposition process of niobium oxide thin film for lithium-ion batteries"

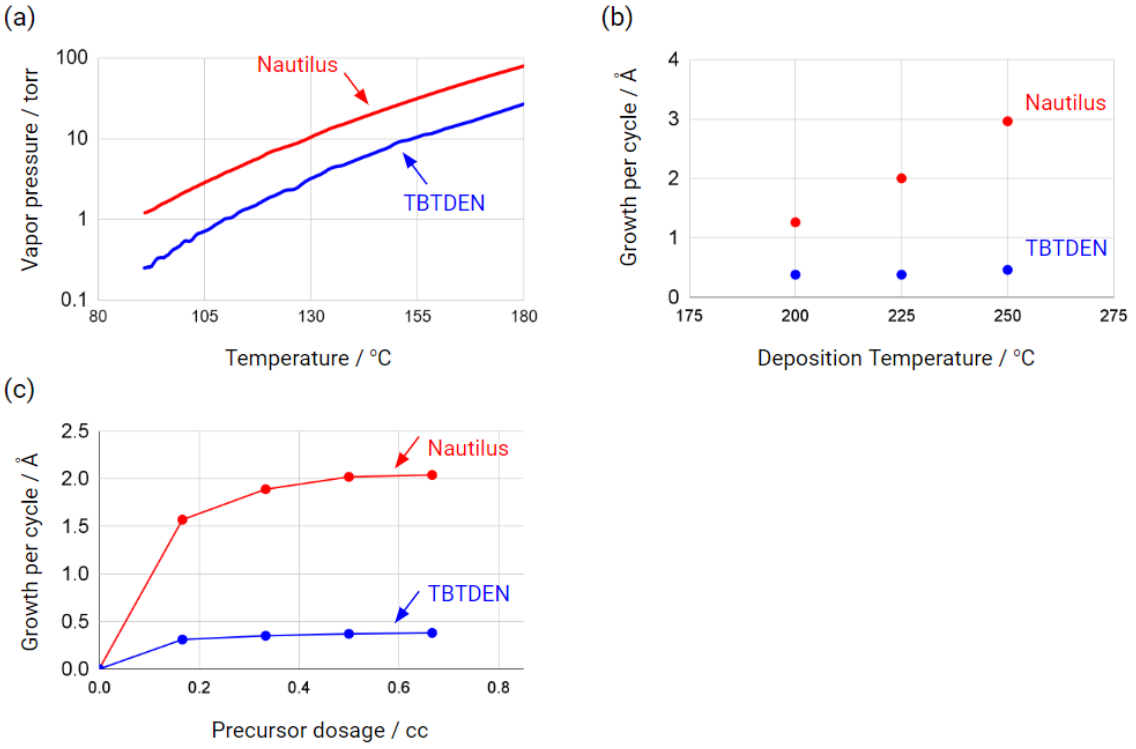

Figure 1. (a) Vapor pressure for TBTDEN and Nautilus. (b) The GPC of Nb_2O_5 on Si wafer as a function of temperature for TBTDEN and Nautilus. (c) The GPC as a function of precursor dosage for TBTDEN and Nautilus. The deposition temperature was 225°C and ozone was used as a co-reactant.

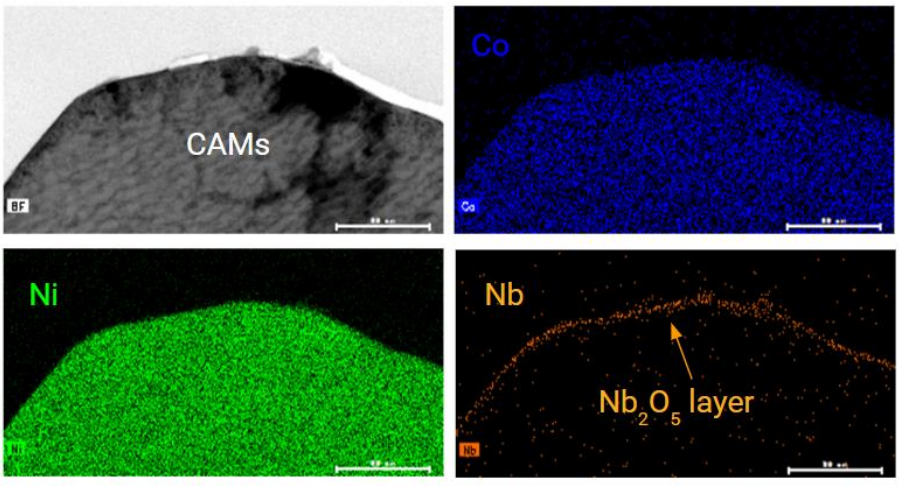

Figure 2. Images of the elemental mappings of the Nb_2O_5-coated $Li(Ni_{0.8}Co_{0.1}Mn_{0.1})O_2$ sample.